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**CROSS-REFERENCE TO RELATED APPLICATIONS**

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This is a Divisional application of co-pending prior U.S. Application No. 09/439,675 (Att. Dkt. No.: LAM1P124/P0558), entitled "TEMPERATURE CONTROL SYSTEM FOR PLASMA PROCESSING APPARATUS," filed on November 15, 1999, the disclosure of which is incorporated herein by reference.

This application also claims the benefit of U.S. Provisional Application No. 60/165,496 (Att. Dkt. No.: LAM1P124P/P0558P), entitled "PROCESSING CHAMBER WITH TEMPERATURE CONTROL," filed November 15, 1999, and incorporated herein by reference. This application is also related to the following U.S. Patent Applications:

- i) Application No.: 09/439,661, entitled "IMPROVED PLASMA PROCESSING SYSTEMS AND METHODS THEREFOR" (Attorney Docket No.: LAM1P122/P0527), filed November 15, 1999.
- ii) Application No.: 09/470,236, entitled "PLASMA PROCESSING SYSTEM WITH DYNAMIC GAS DISTRIBUTION CONTROL" (Attorney Docket No.: LAM1P123/P0557), filed November 15, 1999.
- iii) Application No.: 09/440,418, entitled "METHOD AND APPARATUS FOR PRODUCING UNIFORM PROCESS RATES" (Attorney Docket No.: LAM1P125/P0560), filed November 15, 1999.
- iv) Application No.: 09/440,794, entitled "MATERIALS AND GAS CHEMISTRIES FOR PLASMA PROCESSING SYSTEMS" (Attorney Docket No.: LAM1P128/P0561-1), filed November 15, 1999.
- v) Application No.: 09/439,759, entitled "METHOD AND APPARATUS FOR CONTROLLING THE VOLUME OF PLASMA" (Attorney Docket No.: LAM1P129/P0561-2), filed November 15, 1999.

Each of the above-identified patent applications is incorporated herein by reference.